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(12) **United States Patent**
Tsuchimura et al.(10) **Patent No.:** **US 10,007,180 B2**(45) **Date of Patent:** **Jun. 26, 2018**(54) **NEGATIVE RESIST COMPOSITION, RESIST FILM USING SAME, PATTERN FORMING METHOD, AND MASK BLANK PROVIDED WITH RESIST FILM**(71) Applicant: **FUJIFILM Corporation**, Tokyo (JP)(72) Inventors: **Tomotaka Tsuchimura**, Shizuoka (JP);
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(2013.01); **G03F 1/76** (2013.01); **G03F 7/0045** (2013.01); **G03F 7/0046** (2013.01);
G03F 7/0382 (2013.01); **G03F 7/20**
(2013.01); **G03F 7/40** (2013.01)(58) **Field of Classification Search**

None

See application file for complete search history.

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Primary Examiner — Martin J Angebrannndt(74) *Attorney, Agent, or Firm* — Sughrue Mion, PLLC(57) **ABSTRACT**

A negative resist composition includes an onium salt compound (A) containing a nitrogen atom in its cation moiety, a compound (B) that is configured to produce an acid when exposed to actinic rays or radiation, and a compound (C) containing an acid-crosslinkable group.

12 Claims, No Drawings